

L Number	Hits	Search Text	DB	Time stamp
7	14031	(photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 09:05
8	2507	((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:41
9	948	((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:41
10	503	((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:41
11	77	((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:42
13	48	((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.) and align\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:44

14	35	(((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.) and align\$4) and pattern\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:44
15	18	(((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.) and align\$4) and pattern\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:48
16	17	(((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.) and align\$4) and pattern\$1) and (mask\$4 with pattern\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 08:50

17	29	((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.) not ((((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.) and align\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 09:03
19	426	(((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) not ((((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 09:03

20	115	((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) not ((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.)) and ((photoresist or photosensitive) adj layer\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 09:11
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21	311	<p> ((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) not (((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.)) not ((((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) not ((((((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and 347/\$.ccls.)) and ((photoresist or photosensitive) adj layer\$1)) </p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/29 09:15
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22	445	<p>(((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) not (((photoresist or photosensitive) and (mask\$4 or print\$4 or record\$4) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4)) and ((circul\$6 or rotat\$5) same (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1))) and ((jet\$4 or eject\$4 or discharg\$4) same (mask\$4 or print\$4 or record\$4) same (photosensitive or photoresist))) and ((circul\$6 or rotat\$5) with (stage\$1 or table\$1 or substrate\$1 or wafer\$1 or objet\$1)))</p>	<p>USPAT; US-PGPUB; EPO; JPO; DERWENT</p>	2004/10/29 09:16
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